

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	35	("2882209" "4304641" "4120771" "5168887" "5302256" "5544421" "5605866" "5620581" "5664337" "5678620" "5744019" "5762751" "5788454" "5882168" "5972192" "5980706" "5985126" "6001234" "6004440" "6004828" "6024857" "6090711" "6091498" "6099712" "6110346" "6126798" "6132857" "6139712" "6156167" "6159354" "6179983" "6197181" "6203582" "6228231" "6391166").PN.	US-PGPUB; USPAT	ADJ	ON	2006/06/01 15:21
L2	254099	semiconductor substrate or semiconductor wafer or semiconductor with (wafer or substrate)	US-PGPUB; USPAT	ADJ	ON	2006/06/01 13:54
L3	432742	metal deposition or ((deposit\$4 or electroplat\$ or electrodeposit\$4 or plat\$4 or electrochemical\$3 deposit\$4 or electrochemical\$3 plat\$4 or electrolytic\$3 deposit\$4 or electrolytic\$3 plat\$4) with metal)	US-PGPUB; USPAT	ADJ	ON	2006/06/01 13:58
L4	81429	2 and 3	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:01
L5	116748	(wafer or substrate) with (holder or fixture or workholder or receptacle or support)	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:03
L6	17197	4 and 5	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:04
L7	409954	(inlet and outlet) or (entrance and exit)	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:05
L8	2588	6 and 7	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:06
L9	3960	anode same (electroplat\$4 solution or plat\$4 solution or electroplat\$4 fluid or plat\$4 fluid or plat\$4 bath or electroplat\$4 bath)	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:08
L10	135	8 and 9	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:10
L11	6339974	@pd<"19990421"	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:10
L12	4	10 and 11	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:19
L13	563	8 and 11	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:56
L14	732	204/297.01,297.06,297.07,297.08,297.09,297.1,297.12,297.14.ccls.	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:58

## EAST Search History

L15	506	11 and 14	US-PGPUB; USPAT	ADJ	ON	2006/06/01 14:58
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## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	"6261433".pn.	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:28
L2	57127	backside	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:28
L3	1	1 and 2	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:28
L4	253	fluid basin	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:28
L5	0	1 and 4	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:29
L6	40	flow adjustment member	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:30
L7	0	1 and 6	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:29
L8	2095	flow adjustment	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:30
L9	0	1 and 8	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:30
L10	7929	flow adjust\$4	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:30
L11	1	1 and 10	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:33
L12	156	(first current density) and (second current density)	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:33
L13	0	1 and 12	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:36
L14	137	deposition cycle and current density	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:36
L15	6	low current density same initial plating	US-PGPUB; USPAT	ADJ	ON	2006/06/02 07:37